

## ABSTRACT

## SUBSTRATE CLEANING APPARATUS

A substrate cleaning apparatus includes outer circumference supporting members 32 that support the outer circumference of a rotating substrate W, a swing cleaning member 34 that swings between a first peripheral position B and a second peripheral position B' of the substrate W while passing a center portion A of the substrate W to clean a front surface of the rotating substrate W, and an elongated supporting member 36 that extends long from a third peripheral position C to a fourth peripheral position C' of the substrate W so as to pass the center portion A and supports the rear surface of the rotating substrate W. The first peripheral position B is disposed between a position D of the outer circumference supporting member 32 of the plurality of outer circumference supporting members 32 and closest to the third peripheral position C and the third peripheral position C.

Fig. 11